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ELECTRONIC CHEMICALS

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Wednesday, June 5, 2002

Document Control Office (7407),
Office of Pollution Prevention and Toxics (OPPT),
Environmental Protection Agency (EPA),
1200 Pennsylvania Ave., NW.
Washington, DC 20460.

Subject: Comments on Proposed Significant New Use Rule (SNUR) for Perfluoroalkyl Sulfonates; Docket Control Number OPPTS-50639C

Dear Sir or Madam:

Air Products Electronic Chemicals (APEC) is a supplier of materials to the semiconductor industry. One of the many materials APEC supplies is developer. Developer is an ancillary product utilized in the photolithography process to produce semiconductors. As a supplier of this product, we desire to comment on the above-referenced proposed SNUR. Specifically, we are seeking clarification of an exemption to the proposed SNUR. The exemption, as published on page 2 of a March 11, 2002 letter from Charles M. Auer, Director, Chemical Control Division of the EPA reads:

"*As a component of a photoresist substance, including a photo acid generator or surfactant, or as a component of an anti-reflective coating used in a photomicrolithography process to produce semiconductors or similar components of electronic or other miniaturized devices.*

It is unclear to us if developer, including any PFAS surfactant components of developer, is included in this exemption. The EPA Technical Contact for this SNUR, Mary F. Dominiak, was contacted in an attempt to clarify the exemption. She explained that the exemption was meant to reflect an exemption requested by the semiconductor industry as represented by Semiconductor Industry Association (SIA) and Semiconductor Equipment and Materials International (SEMI). This request was made in the form of a document described by EPA as a "Mass Balance Data Document." This document was requested and received from the EPA's Non-Confidential Information Center. It consists of a letter from SIA and SEMI to the EPA's Office of Pollution Prevention and Toxics, Docket Number OPPTS-50639, dated October 3, 2001. Key points made by this document include:

"*...PFAS-based materials are critical in two applications within the photolithography process: (1) photoresists; and (2) anti-reflective coatings (ARC's).* "

"*On-going chemical stewardship related to the higher homologues will also eliminate the need to use developer containing these substances, a step that greatly reduces the environmental release of PFOS (perfluorooctylsulfonates) moieties.*"

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*"The SIA/SEMI coalition has developed specific regulatory language to implement the exemption that it believes is appropriate for photolithography...It would apply only to SNUR chemicals used as components of photoresists or ARC's, or as intermediates used to produce those materials...**The exemption does not include developer** or polyimide, two inputs to photolithography that we have previously identified."*

Based on the above, it appears that developer, including any PFAS surfactant components of developer, is not covered under this exemption. We are requesting that the EPA clarify the language in the SNUR to more clearly indicate what this exemption covers, and, in this case, what it does not.

It is my understanding that the comment period originally due to close on April 10, 2002, has been extended to July 9, 2002. I hope you find our comments of value and I look forward to your response. If you should have any questions, please contact me at the phone number or e-mail address listed below.

Sincerely,

Randy Skow

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